forming a surface relief pattern on the first support;

applying a conformable material over the surface relief pattern;

pressing said conformable material using a second support and allowing the conformable material to solidify and to adhere to said second support;

once said conformable material has adhered to said second support, pulling said second support with said conformable material adhered thereto, away from said first support to leave a patterned area in the conformable material that is based on said surface relief pattern and to leave said first support.

4. (Amended) The method as in claim 3, wherein said conformable material includes an elastomer.

5. (Amended) The method as in claim 3, further comprising etching indented areas which are formed by contact with said surface relief areas, said etching continuing until said indented areas extend through to said second support.

6. (Amended) The method as in claim 3, where said second support is porous, and further comprising initially blocking pores prior to said pressing of said second support, and unblocking the pores after said pulling.

7. (Amended) A method of making a supported mask, comprising:

obtaining a support;

applying at least one layer of dielectric material to said support; and

exposing said layer to patterned light to substantially cause removal of said layer from said support in exposed areas.

Please add the following new claims:

8. (New) The method as in claim 7 wherein the patterned light is UV light.

9. (New) The method as in claim 7 wherein the exposing causes ablation of the exposed areas of the layer.

10. (New) A method of making a supported mask, comprising:

providing a support;

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forming a surface relief pattern on a surface of the support, wherein the pattern has positive and negative features;

applying a flowable conformable material over the surface of the support containing the relief pattern;

pressing the flowable conformable material against the surface of the support to remove at least a portion of any conformable material that is located over positive features of the surface relief pattern;

solidifying and bonding the flowable conformable material to the support;

removing any residual conformable material that is located over the positive features of the surface relief pattern; and

removing the surface relief pattern from the support while leaving the solidified conformable material bonded to the support.

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11. (New) The method as in claim 10, wherein a flat, non-stick sheet is used to press the conformable material.

12. (New) The method as in claim 10, wherein the residual conformable material is removed by etching.

13. (New) The method as in claim 10, wherein the support comprises a porous medium.

14. (New) The method as in claim 13, further comprising:

forming a barrier layer on the support prior to forming the surface relief pattern; and

removing the barrier layer from at least selected areas of the support.

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